



2823

Docket No. AMDP714USAF01159IN THE UNITED STATES PATENT AND TRADEMARK OFFICEIn re **PATENT** application of:

Applicant: Angela Hui, et al.

Application No.: 10/045,354

For: AN INNOVATIVE METHOD OF HARD MASK REMOVAL

Filing Date: November 7, 2001

Examiner: Khiem D Nguyen

Art Unit: 2823

#7/ Amult B  
Angela  
9/14/03REPLY TO OFFICE ACTION DATED APRIL 2, 2003Box Non-Fee Amendment  
Assistant Commissioner for Patents  
Washington, D.C. 20231RECEIVED  
APR 16 2003  
TECHNOLOGY CENTER 2800

Dear Sir:

Favorable reconsideration of the above-identified application is respectfully requested in view of the following amendments and remarks.

AMENDMENTSIN THE CLAIMS:*Please amend claims 1 and 24 as follows below:*

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1. (Amended) A method of stripping a hard mask from a substrate comprising an insulating material exposed within gaps patterned through the hard mask, comprising:
- coating the substrate with a sacrificial material that fills the gaps; and
  - plasma etching to strip the sacrificial material and the hard mask in a single plasma etch process.
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